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1 **Stochastic excitation for high-resolution Atomic Force Acoustic Mi-** 2 **croscopy imaging: a system theory approach.**

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20 **Abstract**

21 In this work, a high-resolution Atomic Force Acoustic Microscopy imaging technique is shown in
22 order to obtain the local indentation modulus at nanoscale using a model which gives a quantita-
23 tive relationship between a set of contact resonance frequencies and indentation modulus through
24 a white-noise excitation. This technique is based on white-noise excitation for system identifica-

25 tion due to non-linearities in the tip-sample interaction. During a conventional scanning, a Fast
26 Fourier Transform is applied to the deflection signal which comes from the photo-diodes of the
27 Atomic Force Microscopy (AFM) for each pixel, while the tip-sample interaction is excited by a
28 white-noise signal. This approach allows the measurement of several vibrational modes in a sin-
29 gle step with high frequency resolution, less computational data and at a faster speed than other
30 similar techniques. This technique is referred to as Stochastic Atomic Force Acoustic Microscopy
31 (S-AFAM), where the frequency shifts with respect to free resonance frequencies for an AFM can-
32 tilever can be used to determine the mechanical properties of a material. S-AFAM is implemented
33 and compared to a conventional technique (Resonance Tracking-Atomic Force Microscopy, RT-
34 AFAM), where a graphite film over a glass substrate sample is analyzed. S-AFAM can be imple-
35 mented in any AFM system due to its reduced instrumentation compared to conventional tech-
36 niques.

37 **Keywords**

38 Atomic Force Microscopy; Fast Fourier Transform; Mechanical properties; System theory; White
39 noise

40 **Introduction**

41 There are many methods to measure mechanical properties at nanoscale, some of them are based
42 on either indentation or any other physical phenomena [1,2]. However, each method has its own
43 limits due to instrumentation capabilities, contact geometries and so forth. Additionally, some
44 of these methods can be destructive or can provide insufficient resolution as dimensions shrink
45 further[1].

46 Atomic Force Microscopy (AFM) has demonstrated to be a fundamental tool in nanotechnology
47 science [3] since this offers a non-destructive alternative for measuring mechanical properties at
48 nanoscale using the small size of the cantilever tip (radius~5-50nm).

49 Conventional AFM methods for mechanical properties measurement are based either on force-
50 displacement curves or resonance frequencies [1]. Force-displacement works better when the stiff-

51 ness of the cantilever is comparable to that of the test material. This is suitable for soft materials
52 loosing effectiveness as the material stiffness increases. On the other hand, the contact resonance
53 method is ideal when the material stiffness is greater, where the cantilever vibration at or near its
54 resonant frequencies is used. This is suitable for stiff materials such as ceramics or metals [1,4].
55 The functionality can be found in the resonant vibrational modes of the cantilever when it is excited
56 either by an external actuator or by an actuator attached to the AFM cantilever holder [1]. When
57 the tip is out of contact with the sample, the resonance modes occur at a specific frequency that de-
58 pends on the geometrical and material properties of the cantilever, on the other hand, when the tip
59 is placed in contact, the resonance modes increase the frequencies due to tip-sample interaction. In
60 this manner, the mechanical properties of the sample can be deduced from these frequency shifts
61 and a suitable model [1,4-10].

62 The methods which use the resonance frequencies are often labeled as acoustic or ultrasonic meth-
63 ods due to frequency of the vibration involved ($\sim 100\text{kHz}-3\text{MHz}$) [1,8,11]. Among them are: ul-
64 trasonic force microscopy (UFM) [12], heterodyne force microscopy [13], ultrasonic atomic force
65 microscopy (UAFM), atomic force acoustic microscopy (AFAM) [1], bimodal AFM [14], reso-
66 nance tracking-Atomic Force Microscopy (RT-AFAM) [6], band excitation [9], dual-frequency
67 resonance-tracking atomic force microscopy [15], nanomechanical holography [2], G-mode [16],
68 triple frequency atomic force microscopy[17] and so on. Even though these methods offer reali-
69 able measurements, these can only measure one or three resonant vibrational modes with a rel-
70 ative frequency resolution, and in some cases the involved instrumentation can be very complex
71 [2,9,15,16,18] making the system excitation restricted to purely sinusoidal signals and to the lock-in
72 time constant, which reduces the time response of the overall measurement when a lock-in ampli-
73 fier is used [9,16,19].

74 In this work, an AFM technique based on resonance frequency shifts is shown where the main ad-
75 vantages of this technique are: requires a reduced instrumentation, offers higher frequency reso-
76 lution at different resonant vibrational modes, obtains more than one vibrational mode in a single
77 step and gives indentation modulus mappings. These tasks are possible when *system theory* [20]

78 is taken into account, specifically the *identification system problem* [21]. Here, a mathematical
79 model, which describes the free/contact cantilever resonance frequencies, is obtained when the tip-
80 sample interaction is perturbed by a stochastic signal. For this reason, the technique is referred to
81 as Stochastic-Atomic Force Acoustic Microscopy (S-AFAM).

82 S-AFAM works as follows: While the commercial AFM is scanning on contact mode convention-
83 ally, the tip-sample interaction is excited by a white-noise signal generated by a function waveform
84 generator equipment through a piezoelectrical actuator below the tip-sample. At the same time, a
85 Fast Fourier Transform (FFT) is computed to the deflection signal from photo-diodes by data ac-
86 quisition equipment for each pixel of the sample, where each FFT spectrum is stored in a hard-disk.
87 This way of measurement does not use a lock-in amplifier which reduces the time response of the
88 overall measurement and enhances the frequency window for analysis. At the end of the scanning,
89 all the acquired FFT spectra make a 128×128 -pixel mapping, where the detection of frequency
90 shifts is recorded with a resolution of 153.8 Hz. Then, an off-line process is carried out using a
91 program routine on Matlab™ which is based on a mathematical model that relates the contact res-
92 onance frequencies with an indentation modulus value when a white-noise excitation is taken into
93 account. This model is based on the Power Spectral Density (PSD), Harmonic Oscillator Model.
94 At the end of the process, an indentation modulus mapping is obtained through this methodology.
95 This paper is organized as follows. First of all, the prototype is described with further details in-
96 cluding the acquisition data process in the *Materials and methods section*. In the next section, the
97 mathematical background is described in *Experimental details* where the Power Spectral Density is
98 described for a free cantilever and a contact cantilever, both cases excited by white-noise signal. In
99 the *Results and discussion section* the obtained images using S-AFAM are shown, explained within
100 further detail and compared to RT-AFAM. Finally, we end with some conclusions about the capa-
101 bilities of the proposed technique.

102 **Materials and methods**

103 S-AFAM takes an optimal instrumentation, which is plugged in to a commercial AFM equipment,
104 see Figure 1. The instrumentation consists of:

- 105 • A SPM, Bruker / Veeco / Digital Instruments Nanoscope IV Dimension 3100 equip-
106 ment is used, this was upgraded with a closed-loop x-y nanopositioning stage (nPoint, Inc.
107 NPXY100), a signal access module (SAM) accessory which was used for signal input/output
108 to the AFM, and supported on a floating air table and equipped with an acoustical isolation
109 chamber which minimizes the external thermal and vibrational disturbances, respectively.
- 110 • Data acquisition and FFT processing were carried out using NI PXIe-1073 equipment, which
111 includes a NI 7961R FPGA, NI 5762 digitizer at 200MS/s/ch, and PXI 6363DAQ from Na-
112 tional Instruments™.
- 113 • White-noise signal is generated by a function waveform generator HP/Agilent 33120A.
- 114 • BudgetSensors™ diamond-coated silicon probes, 450 μm long with a 0.2 Nm^{-1} spring con-
115 stant were used.
- 116 • All experiments were carried out in dry air at a temperature of $21.0 \pm 0.1^\circ\text{C}$ and humidity of
117 $2\% \pm 1\%$.

118 It is very important to define the appropriate signal in order to make the entire system perturbed,
119 this allows to have enough information about the system dynamics. For this work, a stochastic sig-
120 nal is used for the tip-sample excitation because it can extract all the system dynamics, i.e. *persis-*
121 *tent excitation* in the system theory field [22,23].

122 The proposed technique works when a FFT is computed by NI PXIe-1073 equipment taking into
123 account the deflection signal from photo-diodes for a specific point from the sample to be measured
124 during a conventional scanning of 128×128 -pixel in an AFM. Here, while a system is executing
125 this task, HP/Agilent 33120A is exciting the tip-sample through an external piezoelectric actua-
126 tor below the sample using a white-noise signal. White-noise approximation is used for this pur-

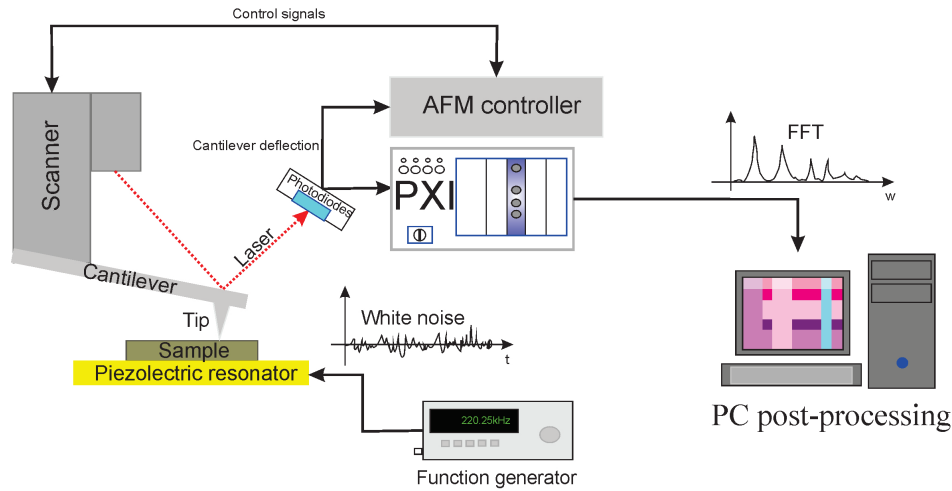


Figure 1: Experimental setup for S-AFAM, using a NI PXIe-1073 equipment and a function waveform generator HP/Agilent 33120A.

127 pose because it can excite the tip-sample system using a 10MHz flat-bandwidth signal generated by
 128 HP/Agilent 33120A equipment [20-24].

129 Once the FFT spectra have been obtained in a 128×128 -pixel mapping, it is saved in a hard-disk
 130 for off-line processing. Each pixel has a FFT spectrum, where they each have at least four reso-
 131 nance frequencies, see Figure 2. An off-line processing is computed for each resonance frequency
 132 taking into account a simple Harmonic Oscillator Model fitting. Finally, the FFT spectra mapping
 133 is transformed into an indentation modulus mapping using a mathematical model based on the
 134 reduced elasticity modulus and PSD model, where the latter is used due to it is the ideal tool for
 135 stochastic process in frequency domain[25].

136 This way of enhancement allows the measurement of several resonance frequencies where other
 137 conventional techniques do not in one single step and without a lock-in amplifier. To show the ca-
 138 pabilities of this technique, a graphite film was deposited on a glass substrate using a sputtering
 139 technique, which was characterized by the conventional method RT-AFAM [6] and by the proposed
 140 technique, S-AFAM.

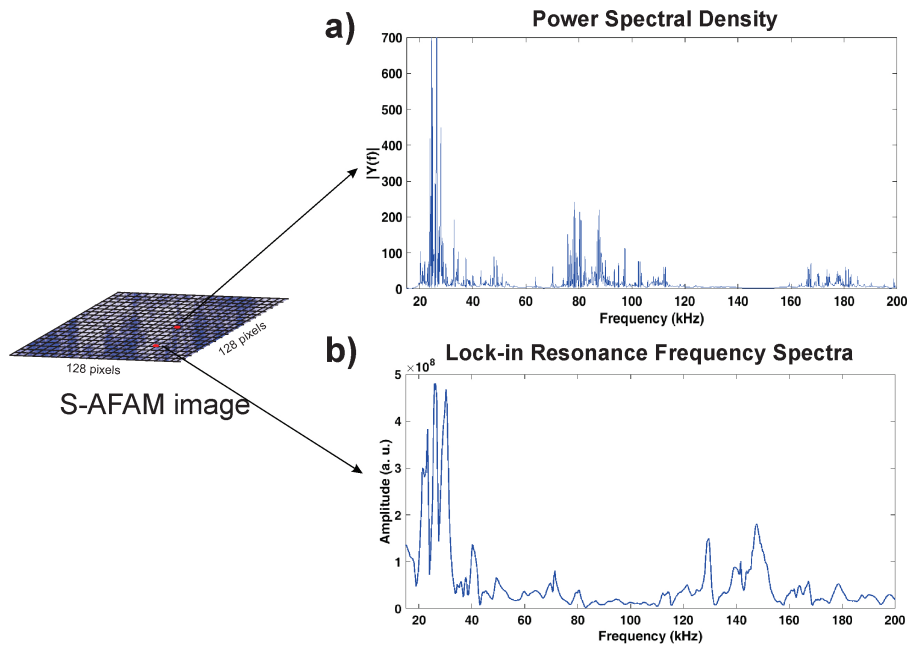


Figure 2: Contact resonance frequencies for a graphite film over glass corning. a) Resonance flexural modes acquired using S-AFAM, b) Resonance flexural modes acquired using a lock-in.

141 Experimental details

142 Dynamic model

143 It is important to have a mathematical model in order to determine that the tip-sample interaction
 144 excited by white-noise can extract the resonance frequencies for a free/contact cantilever. For this
 145 objective, the model by Vazquez et al. [26-28] was taken into account, and then used into a PSD
 146 model to make a transformation from resonance frequency to indentation modulus. This kind of
 147 model is necessary since the white-noise signal belongs to the power signals set. In other words,
 148 these signals offer infinite energy[24,25].

149 For this work, the tip-sample interaction must be studied as a system[20,22], see Figure 3. The in-
 150 put of the system is considered as the excitation signal through a piezoelectrical actuator, which can
 151 be controlled in amplitude and frequency domain, and the output of the system is considered as the
 152 deflection signal from the photo-diodes of the AFM.

153 In this manner, the classical Euler-Bernoulli beam equation is used, which is expressed by Vazquez

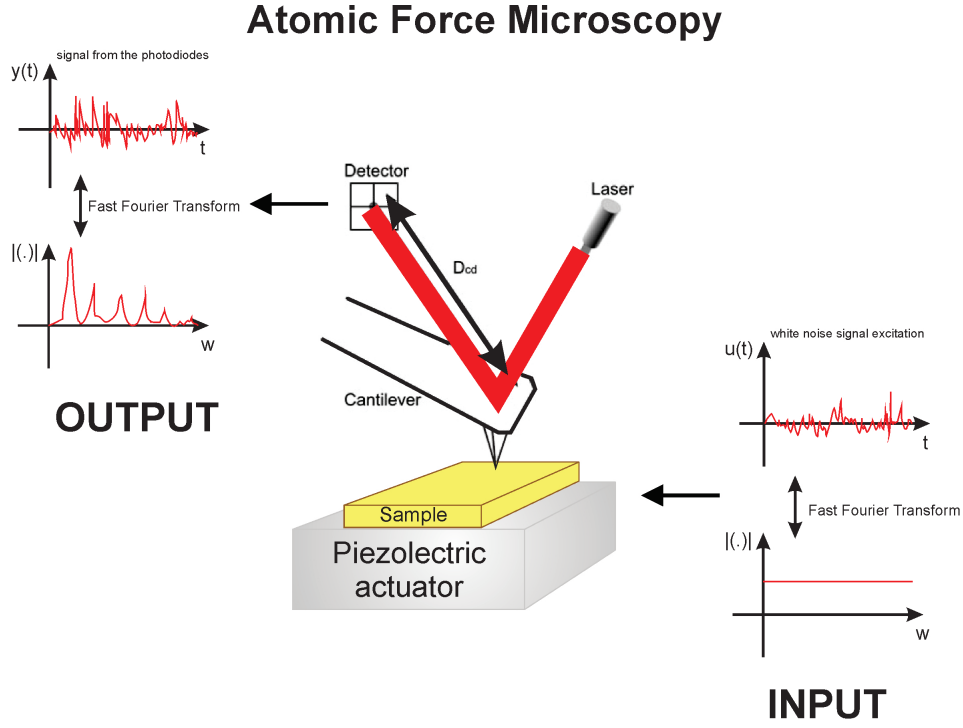


Figure 3: AFM system, piezoelectrical signal excitation is considered as the input, while the deflection signal from the photo-diodes is considered as the output.

154 et al. as [26-28]

$$155 \quad EI \frac{\partial^4 z(x, t)}{\partial x^4} + c \frac{\partial z(x, t)}{\partial t} + m \frac{\partial^2 z(x, t)}{\partial t^2} = -u(t), \quad (1)$$

156 where EI is the flexural stiffness, c corresponds to the damping due to viscous friction, m to the
 157 mass per unit length and $z(x, t)$ is the deflection of the cantilever defined for a displacement toward
 158 the sample, t is time, $x \in [0, L]$, $u(t)$ is a uniform force per unit length acting along the cantilever
 159 and L is the length of the cantilever, respectively. The boundary conditions at the fixed end are

$$160 \quad \begin{aligned} z(x, t) \Big|_{x=0} &= 0, \\ \frac{\partial z(x, t)}{\partial x} \Big|_{x=0} &= 0, \end{aligned} \quad (2)$$

161

162 and at the tip end are

$$\begin{aligned}
 & \frac{\partial^2 z(x, t)}{\partial x^2} \Big|_{x=L} = 0, \\
 & EI \frac{\partial^3 z(x, t)}{\partial x^3} \Big|_{x=L} + f(t) = -q(t),
 \end{aligned} \tag{3}$$

165 where $q(t)$ is the input force acting perpendicular to the cantilever and $f(t)$ is the interaction force
 166 between the cantilever and the surface expressed by Derjaguin-Muller-Toporov (DMT) model [1] as

$$f(t) = -\frac{HR}{6a_0^2} + \frac{4}{3}E^*\sqrt{R}(z_s - z(x, t) + a_0)^{3/2}, \tag{4}$$

168 where H is Hamaker constant, R is the tip radius, E^* is the reduced elastic modulus between the
 169 tip and the sample, a_0 is the interatomic distance and z_s is considered as the distance from the sam-
 170 ple to the tip of the undeflected cantilever, which is described by the force $f(t)$ linearized around a
 171 z_0 point as

$$f(t) = -\frac{\partial f(t)}{\partial z(L, t)} \Big|_{z_0} = -2E^*\sqrt{R}(z_s - z_0 + a_0), \tag{5}$$

173 in this equation $k_{ts} = -(\partial f(t)/\partial z(L, t))|_{z_0}$ represents the contact stiffness. Then, the linearized
 174 model around z_0 according to Equation 3 is

$$EI \left(\frac{\partial^3 z(x, t)}{\partial x^3} \Big|_{x=L} - \frac{\hat{k}_{ts}}{3L^3} z(x, t) \right) = -q(t), \tag{6}$$

176 where

$$k_{ts} = \frac{3EI}{L^3} \hat{k}_{ts}. \tag{7}$$

178 Using the boundary conditions, the Laplace transform is applied to Equation 1, the cantilever de-

179 deflection is described by

$$\begin{aligned} 180 \quad Z(x, s) &= \cosh(\lambda(s)x) [A_1 \cos(\lambda(s)x) + A_2 \sin(\lambda(s)x)] + \\ 181 \quad &\sinh(\lambda(s)x) [A_3 \cos(\lambda(s)x) + A_4 \sin(\lambda(s)x)] + \\ 182 \quad &\frac{U(s)}{4EI\lambda(s)^4}, \end{aligned} \quad (8)$$

183 where

$$184 \quad \lambda(s) = \sqrt[4]{\frac{cs + ms^2}{4EI}}, \quad (9)$$

185 and the constants A_1 , A_2 , A_3 and A_4 can be found using boundary conditions.

186 **Free cantilever transfer function**

187 For the free cantilever response excited by white-noise, Equation 8 has to be considered as a trans-
188 fer function for a PSD treatment. This transfer function describes the relationship between the
189 piezoelectric actuator excitation and the free cantilever deflection according to the system described
190 in Figure 3, this is expressed using some equalities [29] as follows

$$191 \quad \frac{Z_{free}(x, s)}{U(s)} = \frac{-4L^3 \prod_{n=1}^{\infty} \left[1 - \frac{\lambda^4 L^4}{n_n^4} \right]}{24EI \prod_{n=1}^{\infty} \left[1 + \frac{\lambda^4 L^4}{d_n^4} \right]}, \quad (10)$$

192 where n_n and d_n are the n -th roots of

$$193 \quad \tan(n_n) = \tanh(n_n) \mid n_n > 0,$$

$$194 \quad \cos(d_n) \cosh(d_n) = -1 \mid d_n > 0,$$

195 respectively.

196 Thus, Equation 10 is expanded using Equation 9 as

$$197 \quad \frac{Z(x, s)}{U(s)} = \left(\frac{-4L^3}{3EI} \right) \left[\frac{\prod_{n=1}^{\infty} \left(\frac{-mL^4}{4n_n^4} s^2 - \frac{c}{4n_n^4} s + \frac{EI}{L^4} \right)}{\prod_{n=1}^{\infty} \left(\frac{m}{d_n^4} s^2 + \frac{c}{d_n^4} s + \frac{EI}{L^4} \right)} \right], \quad (11)$$

198 Now, PSD has to be computed from Equation 11 since the system is excited by a stochastic sig-
 199 nal [24,25]. For this work, the signal excitation to be considered is white-noise signal because it
 200 features an infinite flat-bandwidth. White-noise is defined as a scalar second-order discrete-time
 201 stochastic process for voltage generated by the function waveform generator, $V_{(-\infty, \infty)}$, and its prop-
 202 erties are

$$203 \quad \eta(k) = E\{V_k\} = 0, \text{ for all } k, -\infty < k < \infty,$$

$$204 \quad R(k, k+l) = E\{V_k V_{k+l}\} = r\delta(k) \text{ for all } -\infty < k, l < \infty.$$

205 where $r \geq 0$, mean $E\{V_k\}$ is the expected value of the random variable $V(k)$, the autocorrelation
 206 $E\{V_k V_{k+l}\}$ is the expected value of the product $V_k V_{k+l}$, and $\delta(k)$ is Dirac delta function [24,25,30].
 207 Then, a PSD must be calculated for each pole and zero. The PSD for a pole is calculated taking
 208 into account a n -th pole from Equation 11 as

$$209 \quad G_{Pn-free}(s) = \frac{\frac{d_n^4}{m}}{s^2 + \frac{c}{m}s + \frac{EId_n^4}{mL^4}},$$

210 which can be transformed into matrix form [20] for sake clarity as

$$211 \quad \begin{bmatrix} \dot{x}_1 \\ \dot{x}_2 \end{bmatrix} = \begin{bmatrix} 0 & 1 \\ -\frac{EId_n^4}{mL^4} & -\frac{c}{m} \end{bmatrix} \begin{bmatrix} x_1 \\ x_2 \end{bmatrix} + \begin{bmatrix} 0 \\ 1 \end{bmatrix} q,$$

$$212 \quad y_1 = \begin{bmatrix} \frac{d_n^4}{m} & 0 \end{bmatrix} \begin{bmatrix} x_1 \\ x_2 \end{bmatrix} + [0]q, \quad (12)$$

213 where \dot{x}_1 is the cantilever deflection, \dot{x}_2 is the derivative for cantilever deflection and q is the same
 214 input force described in Equation 3.

215 The PSD model [24] for a second order system is

$$216 \quad G_{yy}(\omega) = C(-j\omega I - A)^{-1} B G_{\omega\omega}(\omega) B^T (j\omega I - A)^{-T} C^T, \quad (13)$$

217 where ω is the frequency,

$$218 \quad A = \begin{bmatrix} 0 & 1 \\ -\frac{EI d_n^4}{m L^4} & -\frac{c}{m} \end{bmatrix}, B = \begin{bmatrix} 0 \\ 1 \end{bmatrix}, C = \begin{bmatrix} \frac{d_n^4}{m} & 0 \end{bmatrix}, \quad (14)$$

219 $\bar{\lambda} = -j\omega$ as the complex conjugate of λ , the white-noise power is

$$220 \quad E[\omega(t)\omega(\tau)] = V\delta(t - \tau), BG_{\omega\omega}(\omega)B^T = \begin{bmatrix} 0 & 0 \\ 0 & V \end{bmatrix}, \quad (15)$$

221 and V is the voltage amplitude for white-noise signal produced by the function waveform generator.

222 Thus, the Equation 13 for n -th pole becomes

$$223 \quad G_{P_{yy-free}}(\omega) = \frac{\frac{Q d_n^8}{m^2}}{\left(\omega^2 - \frac{EI d_n^4}{m L^4}\right)^2 + \frac{c^2}{m^2} \omega^2}. \quad (16)$$

224 Now, the PSD for a n -th zero is calculated taking into account Equation 11 as

$$225 \quad G_{Z_{n-free}}(s) = \frac{\frac{-m}{4n^4}}{s^2 - \frac{c}{m}s - \frac{4EI n^4}{m L^4}},$$

226 which can be transformed into matrix form for sake clarity as

$$\begin{aligned}
 \begin{bmatrix} \dot{x}_2 \\ \dot{x}_3 \end{bmatrix} &= \begin{bmatrix} 0 & 1 \\ \frac{4EI n_n^4}{mL^4} & -\frac{c}{m} \end{bmatrix} \begin{bmatrix} x_3 \\ x_4 \end{bmatrix} + \begin{bmatrix} 0 \\ 1 \end{bmatrix} q, \\
 y_2 &= \begin{bmatrix} \frac{-m}{4n_n^4} & 0 \end{bmatrix} \begin{bmatrix} x_3 \\ x_4 \end{bmatrix} + [0]q,
 \end{aligned} \tag{17}$$

229 where \dot{x}_3 is white-noise, \dot{x}_4 is the derivative for white-noise.

230 Using the same formula described in Equation 13 for PSD, and the next equalities

$$A' = \begin{bmatrix} 0 & 1 \\ \frac{4EI n_n^4}{mL^4} & -\frac{c}{m} \end{bmatrix}, B' = \begin{bmatrix} 0 \\ 1 \end{bmatrix}, C' = \begin{bmatrix} \frac{-m}{4n_n^4} & 0 \end{bmatrix}, \tag{18}$$

232 $\bar{\lambda} = -j\omega$ as the complex conjugate of λ , and the white-noise power described in Equation 15. The
 233 PSD for a n -th zero becomes

$$G_{Zyy-free}(\omega) = \frac{\frac{Qm^2}{16n_n^8}}{\left(\omega^2 + \frac{4EI n_n^4}{mL^4}\right)^2 + \frac{c^2}{m^2}\omega^2}. \tag{19}$$

235 Finally, taking into account Equation 16 and Equation 19, the PSD for Equation 10 when it is ex-
 236 cited by white-noise is

$$G_{free}(\omega) = \frac{-4L^3}{3EI} \frac{\prod_{n=1}^{\infty} \left[\frac{\left(\omega^2 + \frac{4EI n_n^4}{mL^4}\right)^2 + \frac{c^2}{m^2}\omega^2}{\frac{Qm^2}{16n_n^8}} \right]}{\prod_{n=1}^{\infty} \left[\frac{\frac{Qd_n^8}{m^2}}{\left(\omega^2 - \frac{EI d_n^4}{mL^4}\right)^2 + \frac{c^2}{m^2}\omega^2} \right]}, \tag{20}$$

238 this Equation could possibly be obtained since the model was linearized. For this reason, the PSD
 239 can be calculated for each pole and zero independently in the frequency domain [20,25,31], and
 240 then used altogether for the free cantilever transfer function, Equation 11.

241 **Contact cantilever transfer function**

242 The transfer function for a contact cantilever is defined from Equation 8 as

$$243 \quad \frac{Z_{cont}(x, s)}{U(s)} = \frac{\frac{8L^3}{3} \prod_{n=1}^{\infty} \left[1 + \frac{4\lambda^4 L^4}{n_n^4} \right]}{8EI(1 + \hat{k}_{ts}) \prod_{n=1}^{\infty} \left[1 + \frac{4\lambda^4 L^4}{d_n^4} \right]}, \quad (21)$$

244 where $\hat{k}_{ts} > -1$, n_n and d_n are the n th-roots of

$$245 \quad \tan(n_n) = \tanh(n_n) \mid n_n > 0,$$

$$246 \quad \frac{3\hat{k}_{ts}}{d_n^3} [\sinh(d_n)\cos(d_n) - \cosh(d_n)\sin(d_n)] = 1 + \cos(d_n)\cosh(d_n) \mid d_n > 0,$$

247 respectively.

248 And now, using the same methodology as the last section to obtain the transfer function for a free
 249 cantilever excited by white-noise, the PSD for a contact cantilever is carried out. From Equation 21
 250 the n -th pole is described by

$$251 \quad G_{Pn-cont}(s) = 8EI(1 + \hat{k}_{ts}) \left[1 + \frac{4\lambda^4 L^4}{d_n^4} \right], \quad (22)$$

252 using Equation 13, the PSD for a n -th pole is calculated as

$$253 \quad G_{Pyy-cont}(w) = \frac{\frac{Qd_n^8}{64(1+\hat{k}_{ts})^2 L^8 m^2}}{\left(\omega^2 - \frac{EI d_n^4}{mL^4} \right)^2 + \frac{c^2}{m^2} \omega^2}, \quad (23)$$

254 and also from Equation 21 the n -th zero is described by

$$255 \quad G_{Zn-cont} = \frac{8L^3}{3} \left[1 + \frac{4\lambda^4 L^4}{n_n^4} \right], \quad (24)$$

256 using Equation 13, the PSD for a n -th zero is calculated as

$$257 \quad G_{Zyy-cont}(\omega) = \frac{\left(\omega^2 - \frac{EI n_n^4}{mL^4}\right)^2 + \frac{c^2}{m^2}\omega^2}{\frac{9QE^2I^2n_n^8}{m^2L^8}}. \quad (25)$$

258 Finally, using Equation 23 and Equation 25, the PSD for contact cantilever is calculated for Equa-
259 tion 21 as

$$260 \quad G_{cont}(\omega) = \frac{\prod_{n=1}^{\infty} \left[\frac{\left(\omega^2 - \frac{EI n_n^4}{mL^4}\right)^2 + \frac{c^2}{m^2}\omega^2}{\frac{9QE^2I^2n_n^8}{m^2L^8}} \right]}{\prod_{n=1}^{\infty} \left[\frac{\frac{Qd_n^8}{64(1+k_{ts})^2L^8m^2}}{\left(\omega^2 - \frac{EI d_n^4}{mL^4}\right)^2 + \frac{c^2}{m^2}\omega^2} \right]}. \quad (26)$$

261 Results and Discussion

262 Other similar works in literature give an indentation modulus for each resonance frequency mak-
263 ing a sample to have more than one value for indentation modulus. In this work, Equation 20 and
264 Equation 26 are useful because it gives a quantitative relationship between a set of resonance fre-
265 quencies and a unique indentation modulus through a white-noise excitation. To see the validation
266 of this model, some simulations and measurements are presented.

267 Equation 20 and Equation 26 are simulated with the following numerical data extracted from [27]:
268 $E = 169.7\text{GPa}$, $I = 3.64 \times 10^{-22}\text{m}^4$, $c = 1 \times 10^{-18}\text{kg/ms}$ and $m = 4.08 \times 10^{-7}\text{kg/m}$. For the free
269 cantilever case, the simulation is shown in Figure 4(a). In this figure, a difference in resonance fre-
270 quencies can be seen between a cantilever with $L = 300\mu\text{m}$ and another one with $L = 500\mu\text{m}$, i.e.
271 when the cantilever is shorter, the resonance frequencies increase. Using these computed free reso-
272 nance frequencies, the geometry for a real cantilever can be known if a suitable program routine is
273 used to search for the best cantilever fitted to these frequencies.

274 For the contact cantilever case, the simulation is shown for three cantilevers with a contact stiffness
275 of 10N/m : $L = 300\mu\text{m}$, $L = 400\mu\text{m}$ and $L = 500\mu\text{m}$, see Figure 4(b). The behavior for resonance
276 frequencies is similar to free cantilever, i.e. when the cantilever is shorter, the resonance frequen-

277 cies increase. This result indicates that the length of the cantilever must be taken into account for
 278 the sensitivity, where the range of frequencies depends on the local mechanical properties of the
 279 sample.

280 When a contact cantilever with $L = 400\mu\text{m}$ is taken into account and only its contact stiffness is
 281 changed, it can be seen how the resonance frequencies increase as the contact stiffness does too.

282 Three simulations are shown for contact stiffness \hat{k}_{ts} : 1N/m, 10N/m and 100N/m, see Figure 4(c).

283 These simulations show that it is possible to have a quantitative relationship between a set of reso-
 284 nance frequencies and an indentation modulus value.

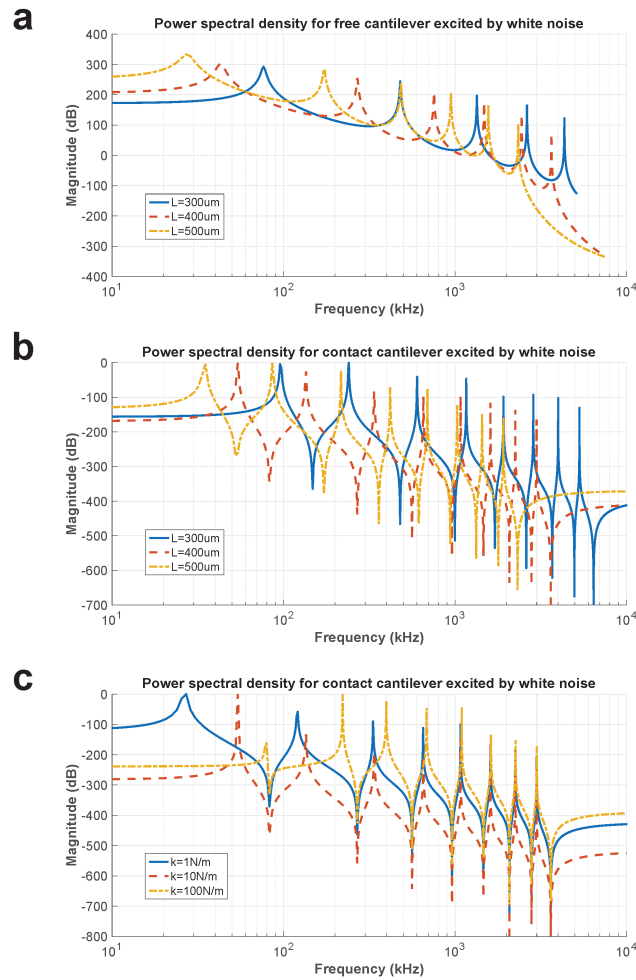


Figure 4: PSD simulation. a) Free cantilever: $L = 300\mu\text{m}$ (blue line), $L = 400\mu\text{m}$ (dashed red line) and $L = 500\mu\text{m}$ (dotted yellow line), b) Contact cantilever: $L = 300\mu\text{m}$ (blue line), $L = 400\mu\text{m}$ (dashed red line) and $L = 500\mu\text{m}$ (dotted yellow line), c) Contact cantilever for $L = 400\mu\text{m}$: $\hat{k}_{ts} = 1\text{N/m}$ (blue line), $\hat{k}_{ts} = 10\text{N/m}$ (dashed red line), $\hat{k}_{ts} = 100\text{N/m}$ (dotted yellow line).

285 Now, the simulated results bring the enough support for an experiment in order to show the capa-
 286 bilities of this technique. First, the geometrical parameters for the experimental cantilever must
 287 be known since the resonance frequency transformation into indentation modulus requires these
 288 values. For this purpose, a resonance frequency spectrum was acquired for free cantilever using
 289 white-noise as excitation signal and the FFT algorithm. These resonance frequencies were fitted
 290 according to a database which was computed using the free cantilever model described in Equation
 291 20, and *particle swarm optimization algorithm*[32-35] in order to obtain the geometrical param-
 292 eters for the experimental cantilever. The database describes each cantilever according to: length
 293 L , width a , thickness b , inertia moment $I = ab^3/12$, linear mass $m = \rho A$, where A is the cross-
 294 section area of the cantilever and $\rho = 2330\text{kg/m}^3$ [36] is the density of the cantilever. The database
 295 has 10000 cantilevers where $L \in [440, 500] \mu\text{m}$, $a \in [40, 50] \mu\text{m}$, $b \in [1, 3] \mu\text{m}$.
 296 The optimization criteria is

$$297 \quad J = e_{rms} = \sqrt{\frac{1}{N} \sum_{n=1}^N (f_n - \hat{f}_n)^2}, \quad (27)$$

298 where e_{rms} is root mean square error, f_n is the n -th measured free resonance frequency, and \hat{f}_n is
 299 the n -th theoretical free resonance frequency. For this work, using this optimization algorithm, the
 300 best cantilever results with the following dimensions: $L = 460\mu\text{m}$, $a = 58\mu\text{m}$, $b = 1.8\mu\text{m}$.
 301 The free resonance frequencies for the fitted experimental cantilever are compared with the exper-
 302 imental ones and with those obtained by using Finite Element Process (FEA) [36], see Table 1.
 303 There is an average error of 3.496% between the experimental frequencies and those obtained by
 304 using the proposed model, meanwhile there is a higher average error of approximately 5.652% be-
 305 tween the experimental frequencies and those obtained by using FEA. Although, there is an almost
 306 homogeneous error of 4% using the proposed model, it can provide a good approximation about
 307 the cantilever geometry using white-noise as an excitation signal. This result reinforces S-AFAM
 308 as a technique for the measurement of mechanical properties.
 309 Also, the k_{lever} was calculated and compared with the fitted experimental cantilever used in this

Table 1: Modeled versus observed dynamic behavior for an AFM free cantilever.

Mode	Experiment (kHz)	FEA (kHz)	Error (%)	Model (kHz)	Error (%)
1	70.102	58.274	16.872	73.490	4.832
2	204.530	198.220	3.085	205.800	0.620
3	386.384	383.350	0.785	403.300	4.378
4	639.992	651.950	1.868	666.600	4.157

310 experiment, the comparison can be seen in Table 2. The first value was obtained from the manufac-
311 turer data, while the second value was obtained using the method by Sader[19], and the third value
312 was obtained using $k_{lever} = \frac{3EI}{L^3}$, where the geometrical values were taken from the fitting process.
313 It is important to notice that there is a good agreement between the Sader method and the proposed
314 model which makes S-AFAM a reliable method.

Table 2: Modeled versus other methods for k_{lever} .

Manufacturer k_{lever} (N/m)	Sader method k_{lever} (N/m)	Model k_{lever} (N/m)
0.2	$0.179 \pm 6.91\%$	$0.1474 \pm 3.49\%$

315 Then, a conventional AFM mapping for a graphite film over a glass substrate was carried out us-
316 ing a white-noise signal as excitation for tip-sample interaction. During this task, each pixel has a
317 FFT computed and stored in a hard-disk. The Figure 4(c) shows that the contact stiffness can be
318 obtained from these contact resonance frequencies, where it is important to notice that a set of res-
319 onance frequencies can provide an unique value for contact stiffness according to Equation 26. For
320 this purpose, a mapping transformation from resonance frequencies to contact stiffness was ob-
321 tained using a database for 8000 values for contact stiffness from 0.5N/m to 4000N/m with a step
322 of 0.5N/m using the geometrical values for the cantilever obtained from the fitting process, see Fig-
323 ure 5.

324 A conventional AFM topography image is shown in Figure 6(a) where each material is indicated by
325 a label, the graphite film was made using sputtering technique with $7nm$ of thickness. Even though

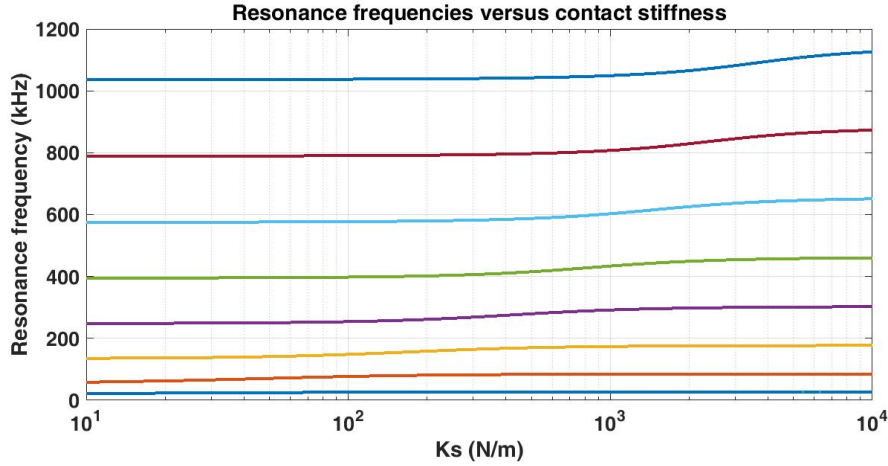


Figure 5: Contact stiffness versus flexural resonance frequencies using a cantilever with geometrical parameters: $L = 460\mu\text{m}$, $a = 58\mu\text{m}$, $b = 1.8\mu\text{m}$.

326 the sample has two materials, it is very difficult to see a difference using conventional AFM mea-
 327 surement. For this reason, a conventional AFM technique based on contact resonance was used, in
 328 this case RT-AFAM [6], where the sample must show two resonance zones: one for glass and the
 329 other one for graphite, respectively. Figure 6(b) shows a RT-AFAM image where the two materials
 330 can be appreciated, but the difference between the materials is not enough.

331 Now, S-AFAM was used to obtain images with higher resolution frequency, making the difference
 332 between graphite and glass visible, see Figure 6(c), (d), (e) and (f). When the frequency window
 333 goes higher, not only a higher difference is appreciated between two materials, but some details
 334 can also be seen, which are attributed to the aggregates and imperfections of the deposition tech-
 335 nique between the glass substrate and the same material deposited on it. In Figure 6(d), one kind
 336 of these details is appreciated in the left-bottom zone where the resonance frequency contribution
 337 is higher for glass than graphite, which could be explained if the contact deposition was deposited
 338 with some imperfections. The maximum difference between two materials is shown in Figure 6(d)
 339 and (e) where the resonance frequency peaks are greater than in any other image. It is important
 340 to notice that Figures 6(c), (d), (e) and (f) were acquired during approximately 3 hours using S-
 341 AFAM, while the same result using RT-AFAM would have taken more than 8 hours with lower
 342 resolution as seen in Figure 6(b).

343 Finally, it is well known that the tip-sample interaction provides information about the contact

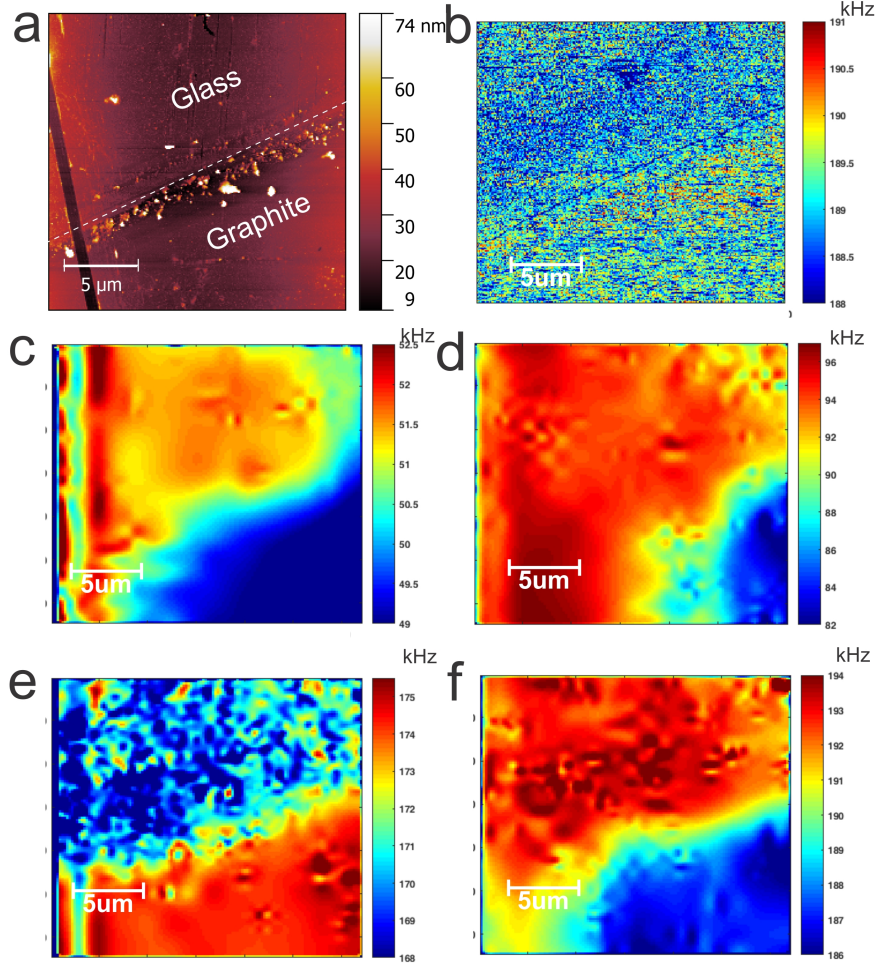


Figure 6: Results for graphite film over glass substrate. a) Conventional AFM topography, b) RT-AFAM for 188-191kHz window, and S-AFAM frequency map for: c) 49-53kHz window, d) 82-97kHz window, e) 168-176kHz window, and f) 186-194kHz window.

344 stiffness, which is product of effective contact and indentation modulus [8,9,18,37-45]. Using
 345 $k = 2aE^*$ and $E^* = \left(\frac{1}{M_{tip}} + \frac{1}{M_{sample}}\right)^{-1}$, where $a \sim 11\text{nm}$ was obtained using the methodol-
 346 ogy by [46], $M_{tip} = 170.33\text{GPa}$ [36] and the proposed model, an indentation modulus mapping is
 347 obtained, see Figure 7. This mapping was computed using the results shown in Figure 6(c), (d), (e)
 348 and (f) and the database shown in Figure 5.

349 In Figure 7 (a) a higher difference between glass and graphite film can be seen when they are com-
 350 pared to RT-AFAM result. Even though the difference is very closed, S-AFAM can detect it a with
 351 higher resolution, see the histogram shown in Figure 7 (b). This difference is due to the glass sub-
 352 strate contribution and the thin thickness of the graphite film, where the indentation modulus are:

353 53.15MPa for glass substrate and 57.875MPa for the graphite film. These results agree with litera-
354 ture [47].

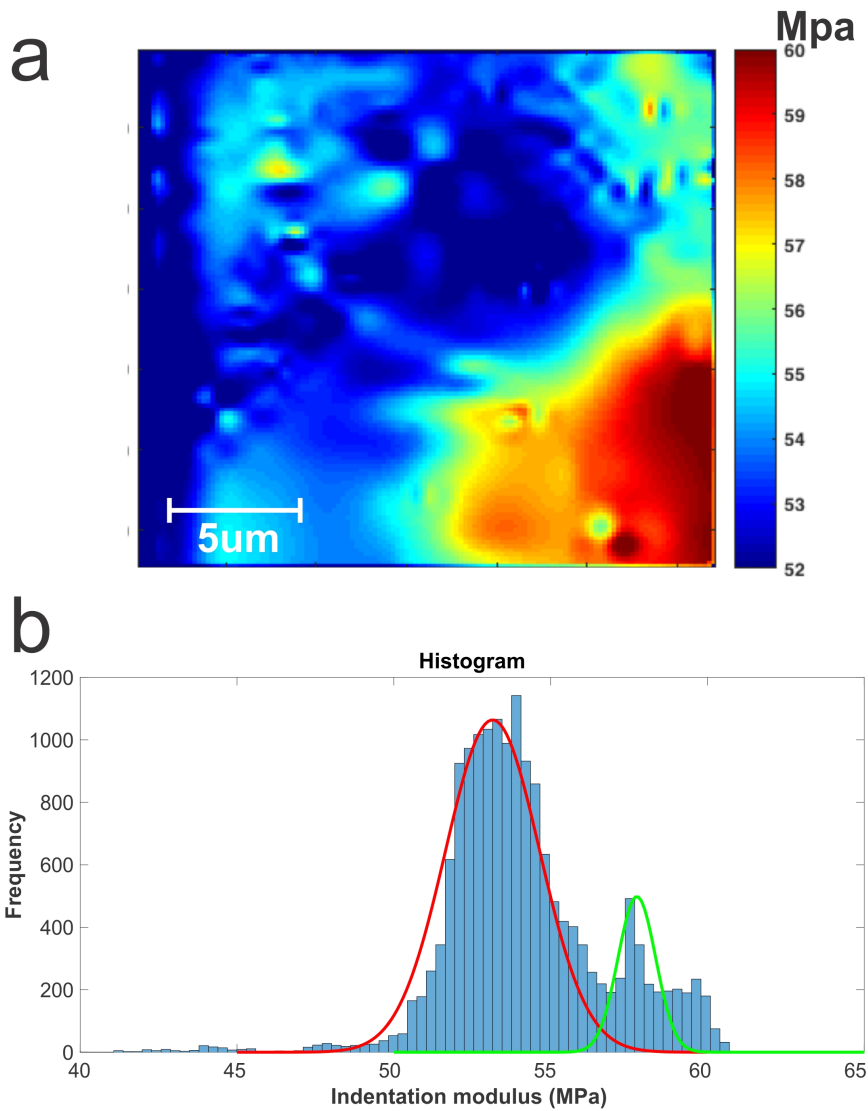


Figure 7: Results for graphite film over glass sample: a) Indentation modulus mapping and, b) histogram for the mapping.

355 The results make S-AFAM suitable for non-homogeneous material when the local mechanical
356 properties over the material have closed resonance frequencies using white-noise. This way of ex-
357 citation perturbs all the resonance frequencies at the same time, making the resonant modes extrac-
358 tion to be acquired in one measurement.

359 Even though the deflection signal from the photo-diodes is weak, when it is Fourier transformed,
360 the amplitude increases significantly in the Fourier domain. This is possible due to the next Fourier

361 transform property [25,31]

$$362 \quad f(t) \leftrightarrow F(\omega), \quad (28)$$

363 for a real constant a ,

$$364 \quad f(at) \leftrightarrow \frac{1}{|a|} F\left(\frac{\omega}{a}\right), \quad (29)$$

365 when $|a| < 1$, it is possible to measure higher resonance frequencies without losing frequency
366 resolution.

367 Theoretically, white-noise signal features an infinite flat-bandwidth which is impossible to gen-
368 erate [34,48]. Fortunately, this can be generated as an approximation using a waveform function
369 generator, which makes white-noise an ideal signal for system identification because it can ex-
370 cite all the system dynamics instantaneously, i.e. it does not require time excitation such as sweep
371 frequency[19]. Otherwise, it would not be possible to obtain using other kind of signals, i.e. *per-*
372 *sistent excitation* [22]. Also, white-noise energy is lower than any other conventional signal avoid-
373 ing either an electrical damage to the piezoelectric actuators or a physical damage to the sample.
374 S-AFAM can be enhanced if a more capable instrumentation in real time is used, which allows an
375 FFT to have a higher computational speed, and if a better white-noise signal generator is used, i.e.
376 thermionic diode, which features a richer packet of frequencies.

377 **Conclusions**

378 S-AFAM can provide more information about aggregates, grain limits, mechanical stress of a grain,
379 and so on when the local mechanical properties are closed, which makes these properties difficult
380 to see when using a conventional technique. This achievement was possible because a white-noise
381 excitation can extract more information about the tip-sample interaction than any other kind of sig-
382 nals using a power spectral density model and system theory. Additionally, S-AFAM does not have
383 to look for a resonance frequency as other conventional techniques do, it only uses a reduced and

384 optimal instrumentation without a lock-in amplifier so that the signal from the photo-diodes is not
385 affected by the time constant of the lock-in amplifier. The resonant modes extraction is acquired
386 in one single step of measurement, and the stored data is minimized in a hard-disk where the time
387 taken for a measurement is important.

388 The results indicate that many contact resonance frequencies allow one indentation modulus value,
389 where many values of indentation modulus would have been existed if other conventional technique
390 would have been used. For this reason, it is important to have more than one vibrational mode
391 of the tip-sample interaction since it provides quantitative knowledge about the contact stiffness,
392 which is necessary in order to make further analysis about local mechanical properties.

393 S-AFAM provides images not only in high-resolution frequency, but also in depth resolution com-
394 pared to conventional techniques, which loses resolution due to instrumentation and kind of signal
395 excitation used for experimental purpose. Using S-AFAM, allows to carrying out depth analysis
396 about local mechanical properties with a suitable model capable of making a relation between reso-
397 nance frequency and indentation modulus.

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